

Serial No. 09/633,857
Art Unit: 1765

IN THE CLAIMS:

Kindly amend claims 1 and 11, and cancel claims 2 and 12, all without prejudice, to appear as follows:

B1 sub 3
1. (Twice Amended) A method of depositing a film containing silicon on a crystalline silicon surface, said method including steps of
introducing a gas containing precursor material into a reaction vessel,
adsorbing an activated species formed from said precursor material on said crystalline silicon surface, and
determining a partial pressure of hydrogen in residual gases as said activated species is deposited on said crystalline silicon surface,
controlling in real time at least one of temperature and mass flow of said precursor material in said reactor vessel in response to said partial pressure of hydrogen, wherein said step of controlling includes controlling in real time at least one of temperature and mass flow according substantially to the temperature profile and a gas flow profile depicted in regions I, II, IV and VI of Figure 4.

B2 sub 1
11. (Twice Amended) Apparatus for depositing a film containing silicon on a crystalline silicon surface including
means for introducing a gas containing precursor material into a reaction vessel such that an activated species formed from said precursor material is adsorbed on said crystalline silicon surface, and

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means for determining a partial pressure of hydrogen in residual gases as said activated species is deposited on said crystalline silicon surface,
means for controlling in real time at least one of temperature and mass flow of said precursor material in said reactor vessel in response to said partial pressure of hydrogen, wherein said means for controlling includes means for controlling in real time at least one of temperature and mass flow according to the temperature profile and a gas flow profile depicted in regions I, II, IV and VI of Figure 4.

REMARKS

Applicant made self-explanatory amendments to independent claims 1 and 11.

35 USC 112

Applicant respectfully traverses the Examiner's rejection with respect to claims 1, 11 (twice amended). Respectfully, Applicant believes the profiles as set forth in Figure 4 (regions I, II, IV and VI) of the application as filed are definite, to one skilled in the art.

35 USC 103

To the extent any art rejection continues to be applied against claims 1, 11 (as amended), reconsideration is respectfully requested.

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